

A facile solvent free Synthesis Route for the Assembly of Highly CO₂ Selective and H₂S tolerant NiSIFSIX Metal-Organic Framework.

*Osama Shekhah, Youssef Belmabkhout, Karim Adil, Prashant Bhatt, Amy J. Cairns, and Mohamed Eddaoudi **

Supplementary Information

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I. Structure refinement

Powder X-ray diffraction (PXRD) measurements were carried out at room temperature on a PANalytical X'Pert PRO diffractometer 45kV, 40mA for CuK α ($\lambda = 1.5418 \text{ \AA}$), from 8 to 80° with a scan speed of 1.0° min⁻¹ and a step size of 0.02° in 2 θ .

The indexation of the PXRD diagram, carried out using the McMaille software,¹ yielded a primitive tetragonal cell (M(20)= 42.4 and F(20)= 64.2 (0.0139, 36)). The cell parameters, a= b= 7.015(1) \AA , c = 7.669(1) \AA , were refined by a whole powder pattern fit using the Le Bail method,² implemented in the FULLPROF software,³ and were consistent with those of the previously described SIFSIX-3-Cu. Hence, atomic positions of the latter were used as structure solution. The final Rietveld refinement permitted access to satisfactory results: $R_{\text{Bragg}} = 0.010$ and $R_{\text{Factor}} = 0.096$ (Figure S1). The crystallographic data and refinement parameters of SIFSIX-3-Ni are summarized in the Table S1.

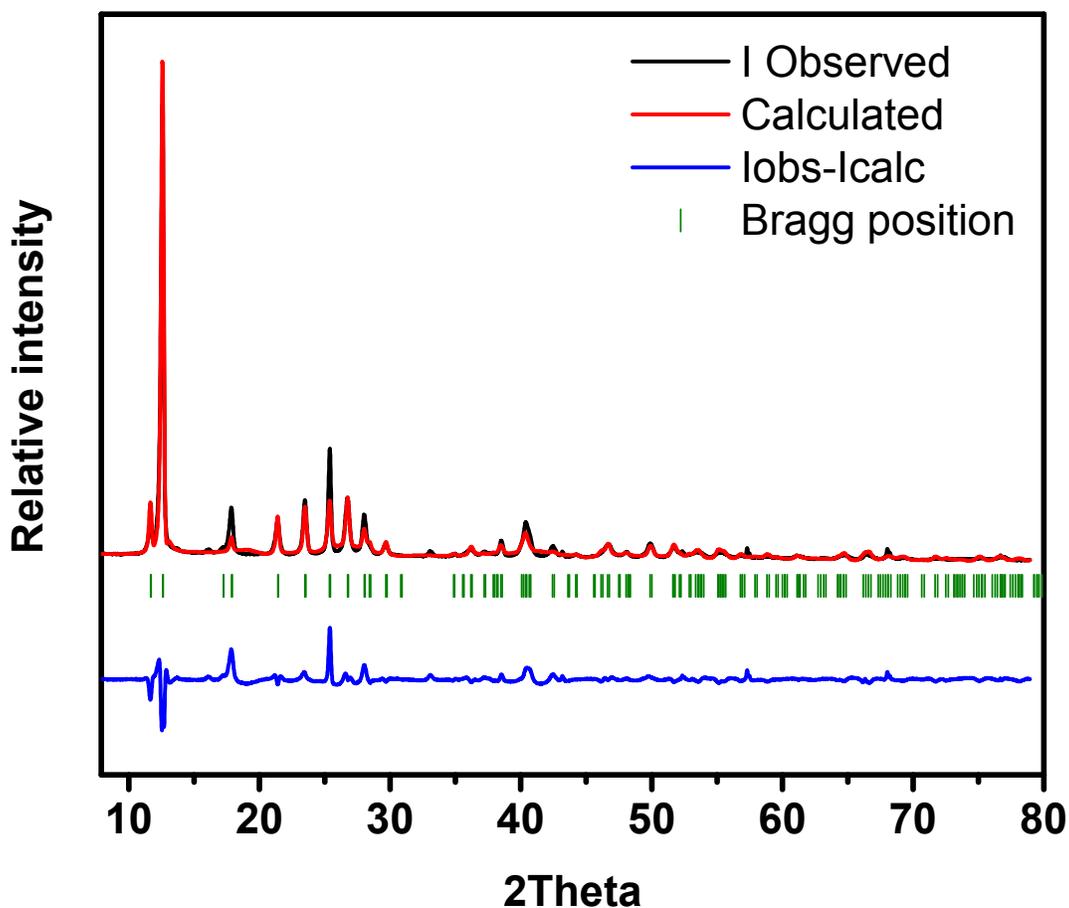


Figure S1: Rietveld refinement of SIFSIX-3-Ni

Table S1: Crystallographic data of **SIFSIX-3-Ni**

Compound	SIFSIX-3-Ni
Formula	$C_8N_4H_8NiSiF_6$
Formula weight (g.mol ⁻¹)	360.96
Crystal system	Tetragonal
Space group	P 4/mmm (n° 123)
a (Å)	7.0147(1)
c (Å)	7.669(1)
V (Å ³)	372.34
Z	1
Wavelength λ (Cu K α)	1.5406
Temperature (K)	298
2-theta range (°)	8-80
Number of independent reflections	247
Number of intensity-dependent parameters	17
R _p , R _{wp} , R _B , R _F	0.337, 0.344, 0.104, 0.096

II. SIFSIX-3-Ni stability after H₂S or H₂O treatment

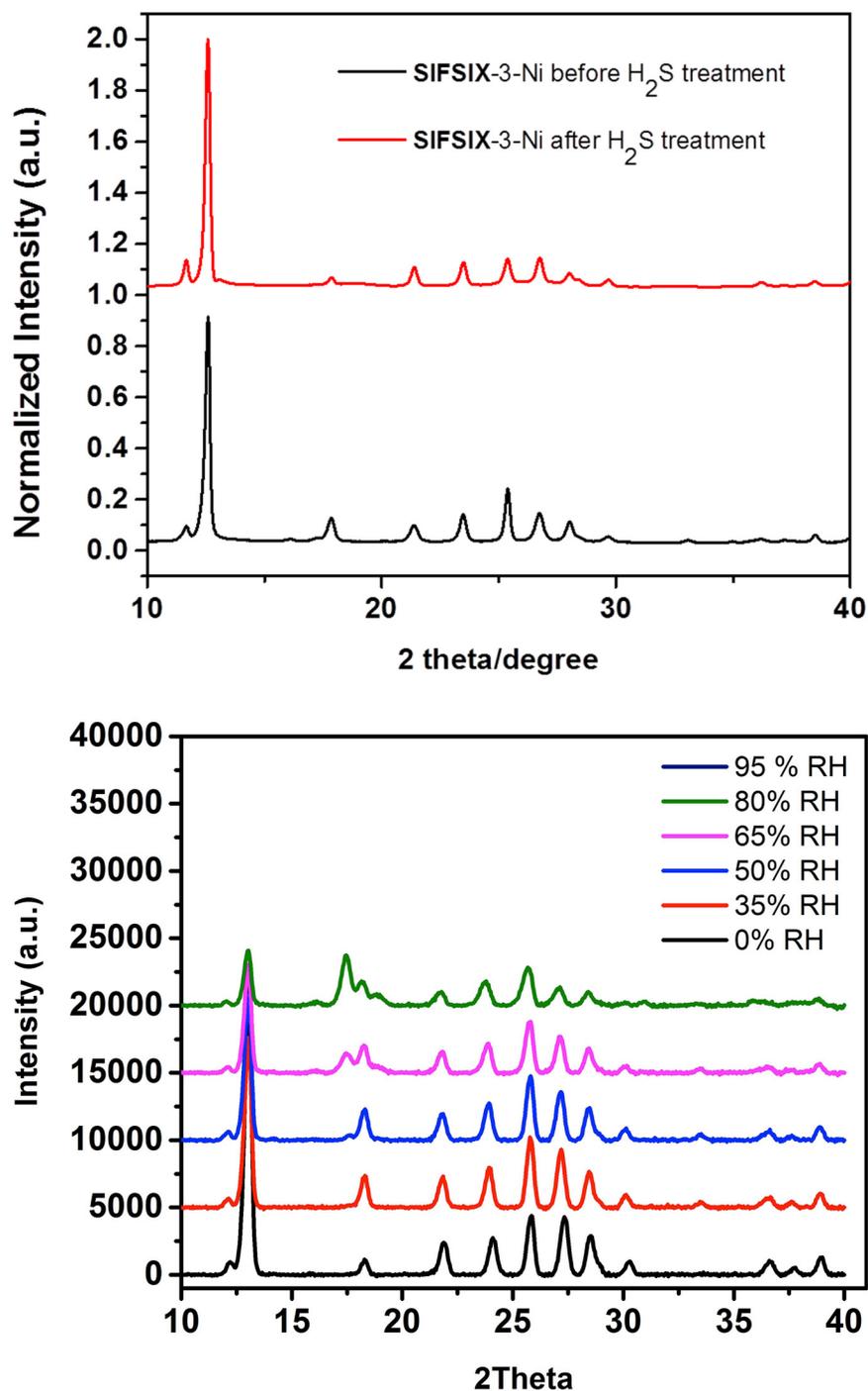


Figure S2: PXRD for SIFSIX-3-Ni after H₂S treatment (top) and H₂O exposure (bottom).

III. Low-Pressure Gas Adsorption Measurements

Homogenous microcrystalline sample of SIFSIX-3-Ni was activated by washing as-synthesized powder with 3 x 20 mL of methanol. In a typical experiment, approximately 30 mg of sample was transferred with solvent in to a 9-mm large bulb glass sample cell and dried under the dry N₂ flow. The sample was first evacuated at room temperature using a turbo vacuum pump for 8 h and then gradually heated to 105 °C, held for 8 h and cooled to room temperature.

The determination of the isosteric heats of adsorption (Q_{st}) for CO₂ was estimated by applying the Clausius-Clapeyron expression using the CO₂ adsorption isotherms measured at 258, 273, 288 and 298 K.

III.1 Isosteric heats of adsorption for SIFSIX-3-Ni

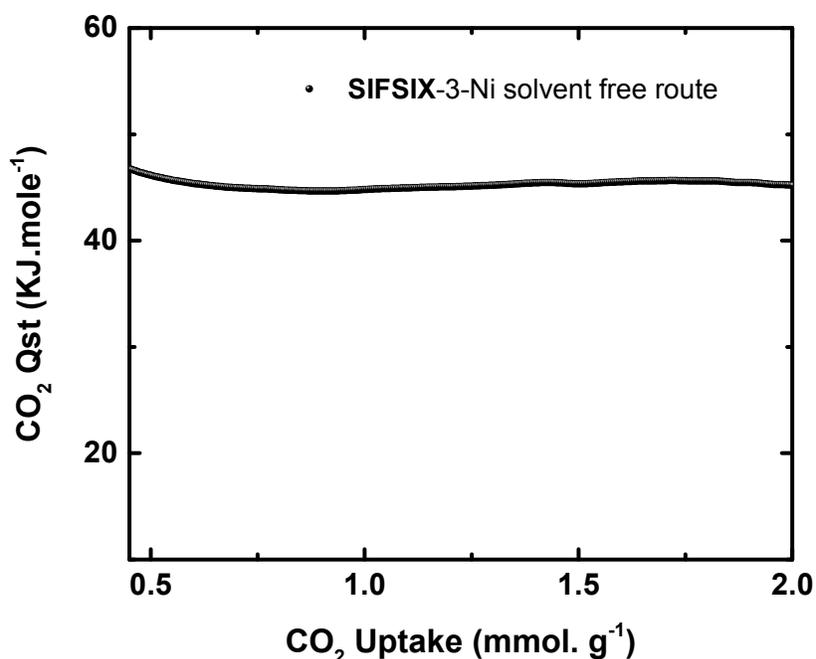


Figure S3: Isosteric heats of adsorption at low coverage for SIFSIX-Ni-3 prepared using solvent free route.

III.2 H₂S sorption isotherm for SIFSIX-3-Ni

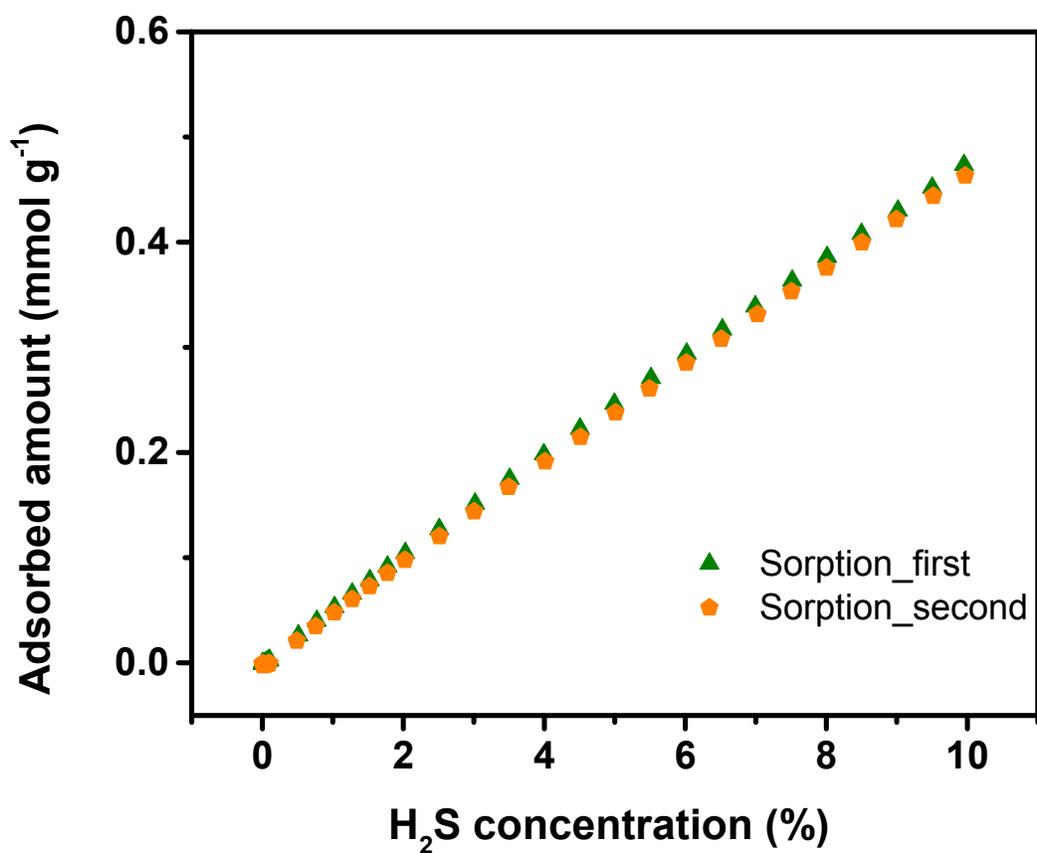


Figure S4: H₂S sorption isotherms for SIFSIX-3-Ni which remains same after two cycles of H₂S sorption.

III.3 CO₂ sorption isotherm for SIFSIX-3-Ni after H₂S exposure

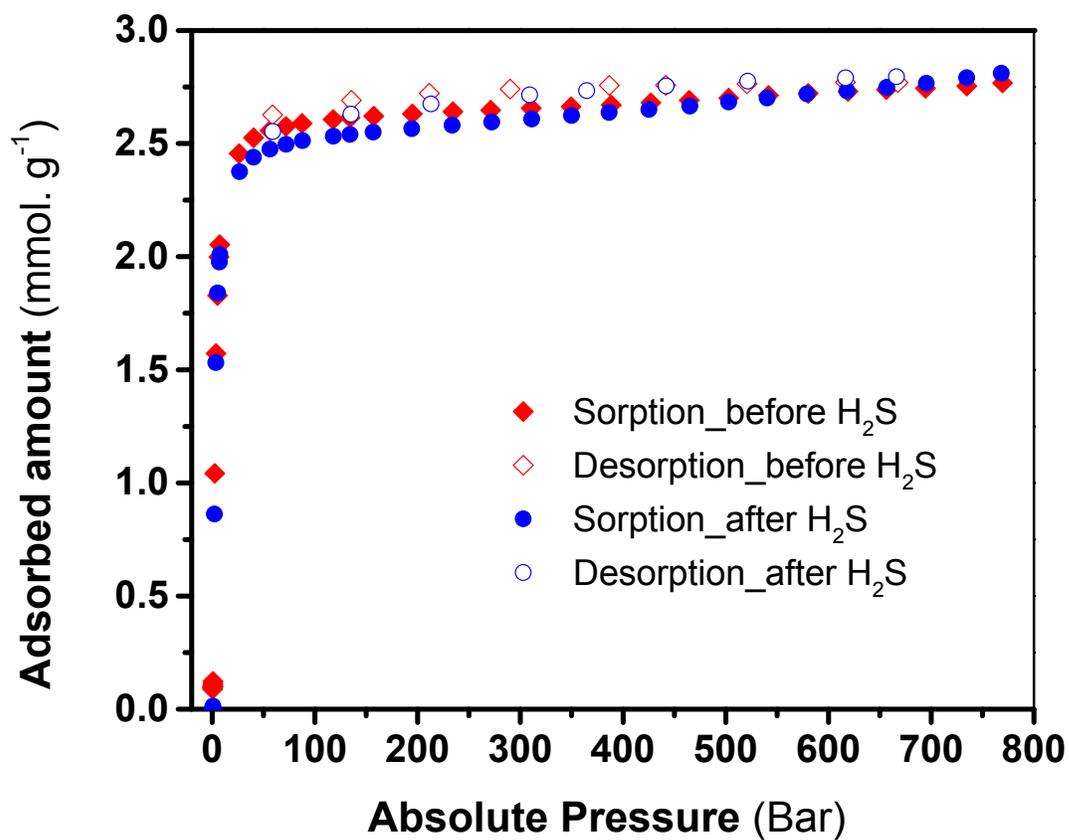


Figure S5: CO₂ sorption isotherms for SIFSIX-3-Ni which remains the same after H₂S sorption.

IV. References

1. Le Bail, A. Monte Carlo indexing with McMaille. *Powder Diffraction* **19**, 249-254 (2004).
2. Le Bail, A., Duroy, H. & Fourquet, J. L. *Ab-initio* structure determination of LiSbWO₆ by X-ray powder diffraction. *Materials Research Bulletin* **23**, 447-452 (1988).
3. Rodriguez-Carvajal, J. Abstracts of the Satellite Meeting on Powder Diffraction of the XV Congress of the IUCr, 127 (1990).